



# Espacenet

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MATERIAL FOR FORMING RESIST-PROTECTING FILM FOR IMMERSION EXPOSURE PROCESS,  
RESIST-PROTECTING FILM MADE OF THE PROTECTING FILM FORMING MATERIAL, AND  
METHOD FOR FORMING RESIST PATTERN USING THE RESIST-PROTECTING FILM

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### Abstract of JP 2005099648 (A)

**PROBLEM TO BE SOLVED:** To provide a material for forming a resist-protecting film for immersion exposure process which is preferably used in an immersion exposure process wherein there is used a nonaqueous liquid with high transparency and high refractive index as typified by fluorine-containing liquids. ; **SOLUTION:** The material for forming a resist-protecting film for immersion exposure process contains at least one component selected from water-soluble and alkali-soluble film-forming materials. The immersion exposure process is characterized in that the resolution of the resist pattern is improved by exposing a resist film to light via the nonaqueous liquid of a certain thickness which has a refractive index higher than that of the air and is disposed at least on the resist film within the path where a lithography exposure light propagates through to the resist film. ; **COPYRIGHT:** (C)2005 JPO&NCPI

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